

ABSTRACT OF THE DISCLOSURE

Shot exposure of arranging first marks on a photosensitive substrate via a reticle in M rows and N columns (e.g., three rows and three columns) at a predetermined column interval and row interval is repeated $m \times n$ times (e.g., 2×2), thereby forming first marks in $M \times m$ rows and $N \times n$ columns (six rows and six columns) on the photosensitive substrate. M and m are natural numbers which are relatively prime, N and n are natural numbers which are relatively prime, and $M > m$ and $N > n$ hold. Shot exposure of arranging second marks on the photosensitive substrate via the reticle in m rows and n columns at the predetermined column interval and row interval is repeated $M \times N$ times, thereby forming second marks in $M \times m$ rows and $N \times n$ columns. Accordingly, $M \times m \times N \times n$ overlay marks are formed from the first and second marks. The misalignment amounts of the first and second marks are measured for each of the $M \times m \times N \times n$ formed overlay marks. The distortion amount is calculated on the basis of the misalignment amounts. Distortion measurement can be performed at a higher precision.